

	L #	Hits	Search Text	DBs	Time Stamp
1	L1	2	("4848141").PN. <i>IDS - bolmanger lstr</i>	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 11:06
2	L2	4	<i>(from IDS, not in)</i> (("6340628") or ("6734533")).PN. <i>parent</i>	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 11:06
3	L3	3	<del>("2007009717").PN.</del> <i>PGPa opps</i>	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 11:07
4	L4	0	<del>L3 and (Kanaya Okayama)</del>	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 11:08
5	L5	2	("20070009717").PN. <i>This case's PG Pub</i>	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 11:08
6	L6	1	<i>↓</i> L5 and (Kanaya Okayama) <i>meaning search</i>	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 11:08

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	L #	Hits	Search Text	DBs	Time Stamp
1	L1	2	("20050194619").PN. <i>from 8/14/07 IDS</i>	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 11:20

*not in ref. tool manager*

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	L #	Hits	Search Text	DBs	Time Stamp
1	L1	2	("20070009717").PN. <i>This case PG Pub</i>	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 12:21
2	L2	1	L1 and (Kanaya Okayama damascene CMP polishing)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 12:23
3	L3	29	(("7164206") or ("6992391") or ("6566757") or ("6846737") or ("6703324") or ("6984581") or ("6432811") or ("6472315") or ("6593650") or ("7115995") or ("7192856") or ("6057226") or ("6417098")).PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 12:25
4	L4	4	L3 and (EB "e-beam" ebeam (e electron) near (beam ray stream gun bombard\$7))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 12:28
5	L5	25	L3 not L4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 12:45
6	L6	113284	(CDO SiOCH SiCOH (oxide dioxide SiO SiO2 "SiO.sub.2" "SiO.sub.2")) near3 ((C carbon organic) near (dop\$7 impurity residue) organic polymer\$7 hybrid)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 13:00

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	L #	Hits	Search Text	DBs	Time Stamp
7	L7	2213	(Dielectric low adj K) near3 ((C carbon organic carbonaceous) near (dop\$7 impurity residue sacrificial) hybrid pore adj form\$5)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 13:00
8	L8	113321	(CDO SiOCH SiCOH (oxide dioxide SiO SiO2 "SiO.sub.2" "SiO.sub.2")) near3 ((C carbon carbonaceous organic) near (dop\$7 impurity residue) organic polymer\$7 hybrid)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 13:01
9	L9	585	(L7 or L8) same(EB "e-beam" ebeam (e electron) near (beam ray stream gun bombard\$7))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 13:02
10	L10	2510	(427/496-507,551,552).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 13:03
11	L11	13	L9 and L10	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 13:03
12	L12	78	L9 and "438"/\$.CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 13:04
13	L13	76	L12 not L11	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 13:05

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	L #	Hits	Search Text	DBs	Time Stamp
14	L14	40	L13 and damascene <i>includes parent's P6 Pub</i>	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 13:05
15	L15	36	L12 not (L11 or L14)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 13:06
16	L16	39	(L9 and (damascene CMP chemical adj mechanical adj polish\$5)) not (L11 or L14 or L15)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 13:08
17	L17	19	(L9 same (interlevel interlayer intern adj (level layer) wiring copper)) not (L11 or L14 or L15)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 13:09
18	L18	51	L16 or L17 <i>Contains these cases P6 Pub</i> <i>2 Copied 10/16/2,331's P6 Pub</i>	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2007/10/16 13:10

Day : Tuesday  
Date: 10/16/2007

Time: 11:42:13

## PALM INTRANET

## Inventor Information for 10/802991

Inventor Name	City	State/Country
WONG, LAWRENCE D.	BEAVERTON	OREGON

Appln Info	Contents	Petition Info	Atty/Agent Info	Continuity/Reexam	Foreign L
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Attorney Docket #  Bar Code #  

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Name Search*

Day : Tuesday  
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**PALM INTRANET**

Time: 11:42:25

## Inventor Name Search Result

Your Search was:

Last Name = WONG

First Name = LAWRENCE

Application#	Patent#	Status	Date Filed	Title	Inventor Name
<u>09820079</u>	<u>7164206</u>	150	03/28/2001	STRUCTURE IN A MICROELECTRONIC DEVICE INCLUDING A BI-LAYER FOR A DIFFUSION BARRIER AND AN ETCH-STOP LAYER	WONG, LAWRENCE
<u>09968459</u>	<u>6992391</u>	150	09/28/2001	DUAL-DAMASCENE INTERCONNECTS WITHOUT AN ETCH STOP LAYER BY ALTERNATING ILDS	WONG, LAWRENCE
<u>10070012</u>	<u>6973297</u>	150	07/29/2002	METHOD AND APPARATUS FOR DOWN-CONVERSION OF RADIO FREQUENCY (RF) SIGNALS WITH REDUCED LOCAL OSCILLATOR LEAKAGE	WONG, LAWRENCE
<u>10070280</u>	<u>7046980</u>	150	07/29/2002	METHOD AND APPARATUS FOR UP-AND DOWN-CONVERSION OF RADIO FREQUENCY (RF) SIGNALS	WONG, LAWRENCE
<del>10328806</del>	Not Issued	161	12/23/2002	Method of making semiconductor devices using carbon nitride, a low-dielectric-constant hard mask and/or etch stop	WONG, LAWRENCE
<u>10363158</u>	<u>7215931</u>	150	08/01/2003	METHOD AND APPARATUS FOR UP-AND-DOWN-CONVERSION OF RADIO FREQUENCY (RF) SIGNALS	WONG, LAWRENCE
<u>11109241</u>	Not Issued	41	04/18/2005	Thin passivation layer on 3D devices	WONG, LAWRENCE
<del>11131740</del>	Not Issued	161	05/17/2005	Dual-damascene interconnects without an etch stop layer by alternating ILDs	WONG, LAWRENCE
<u>11289993</u>	Not Issued	30	11/30/2005	Delta code messaging	WONG, LAWRENCE

no EB  
- no mat  
sp. closed

<u>11733764</u>	Not Issued	25	04/11/2007 Y	PLASMA PROCESS UNIFORMITY ACROSS A WAFER BY APPORTIONING POWER AMONG PLURAL VHF SOURCES	WONG, LAWRENCE
<u>11733767</u>	Not Issued	25	04/11/2007 X	PLASMA PROCESS UNIFORMITY ACROSS A WAFER BY APPORTIONING GROUND RETURN PATH IMPEDANCES AMONG PLURAL VHF SOURCES	WONG, LAWRENCE
<u>11733770</u>	Not Issued	30	04/11/2007 X	PLASMA PROCESS UNIFORMITY ACROSS A WAFER BY CONTROLLING RF PHASE BETWEEN OPPOSING ELECTRODES	WONG, LAWRENCE
<u>11733858</u>	Not Issued	25	04/11/2007 X	PLASMA PROCESS UNIFORMITY ACROSS A WAFER BY CONTROLLING A VARIABLE FREQUENCY COUPLED TO A HARMONIC RESONATOR	WONG, LAWRENCE
<u>11733913</u>	Not Issued	25	04/11/2007 X	PLASMA REACTOR WITH ION DISTRIBUTION UNIFORMITY CONTROLLER EMPLOYING PLURAL VHF SOURCES	WONG, LAWRENCE
<u>11733984</u>	Not Issued	25	04/11/2007 X	METHOD OF PROCESSING A WORKPIECE IN A PLASMA REACTOR WITH VARIABLE HEIGHT GROUND RETURN PATH TO CONTROL PLASMA ION DENSITY UNIFORMITY	WONG, LAWRENCE
<u>11734040</u>	Not Issued	25	04/11/2007 X	PLASMA REACTOR WITH WIDE PROCESS WINDOW EMPLOYING PLURAL VHF SOURCES	WONG, LAWRENCE
<u>11738505</u>	Not Issued	25	04/22/2007 X	PLASMA PROCESSING APPARATUS	WONG, LAWRENCE
<u>11738507</u>	Not Issued	25	04/22/2007 X	PLASMA PROCESSING METHOD	WONG, LAWRENCE
<u>11828568</u>	Not Issued	17	07/26/2007 X	PLASMA REACTOR WITH REDUCED ELECTRICAL SKEW USING ELECTRICAL BYPASS ELEMENTS	WONG, LAWRENCE
<u>11828713</u>	Not Issued	17	07/26/2007 X	PLASMA REACTOR WITH REDUCED ELECTRICAL SKEW USING A CONDUCTIVE	WONG, LAWRENCE



				BAFFLE	
<u>60652407</u>	Not Issued	159	02/12/2005	Method, apparatus and kit for attaching artificial flowers to non-blooming live vegetation or other supports	WONG, LAWRENCE
<u>60652713</u>	Not Issued	159	02/14/2005	Method, apparatus and kit for attaching artificial flowers to non-blooming live vegetation on other supports	WONG, LAWRENCE
<u>60654203</u>	Not Issued	159	02/18/2005	Method, apparatus and kit for attaching artificial flowers to non-blooming live vegetation or other supports	WONG, LAWRENCE
<u>60898632</u>	Not Issued	20	01/30/2007	Multi-frequency capacitively coupled plasma source with uniformity control by spectral power apportionment	WONG, LAWRENCE
<u>09516650</u>	<u>6566757</u>	150	03/01/2000	STABILIZATION OF LOW DIELECTRIC CONSTANT FILM WITH IN SITU CAPPING LAYER	WONG, LAWRENCE D.
<del>09537160</del>	Not Issued	<del>161</del>	03/29/2000	Method for modifying the surface of a fluorocarbon	WONG, LAWRENCE D.
<u>09639625</u>	<u>6846737</u>	150	08/15/2000	PLASMA INDUCED DEPLETION OF FLUORINE FROM SURFACES OF FLUORINATED LOW-K DIELECTRIC MATERIALS	WONG, LAWRENCE D.
<u>09745397</u>	<u>6703324</u>	150	12/21/2000	MECHANICALLY REINFORCED HIGHLY POROUS LOW DIELECTRIC CONSTANT FILMS	WONG, LAWRENCE D.
<u>09745705</u>	<u>6984581</u>	150	12/21/2000	STRUCTURAL REINFORCEMENT OF HIGHLY POROUS LOW K DIELECTRIC FILMS BY ILD POSTS	WONG, LAWRENCE D.
<u>09747701</u>	<u>6432811</u>	150	12/20/2000	Method of forming structural reinforcement of highly porous low k dielectric films by Cu diffusion barrier structures	WONG, LAWRENCE D.
<u>09808758</u>	<u>6472315</u>	150	03/14/2001	METHOD OF VIA PATTERNING UTILIZING HARD MASK AND STRIPPING PATTERNING MATERIAL AT LOW TEMPERATURE	WONG, LAWRENCE D.

<del>10025260</del>	Not Issued	161	12/17/2001	Structural reinforcement of highly porous low k dielectric films by ILD posts	WONG, LAWRENCE D.
10050463	6593650	150	01/15/2002	PLASMA INDUCED DEPLETION OF FLUORINE FROM SURFACES OF FLUORINATED LOW-K DIELECTRIC MATERIALS	WONG, LAWRENCE D.
10153982	7115995	150	05/22/2002	STRUCTURAL REINFORCEMENT OF HIGHLY POROUS LOW K DIELECTRIC FILMS BY CU DIFFUSION BARRIER STRUCTURES	WONG, LAWRENCE D.
10161104	6734533	150	05/30/2002	ELECTRON-BEAM TREATED CDO FILMS	WONG, LAWRENCE D.
10654299	Not Issued	149	09/02/2003	Mechanically reinforced highly porous low dielectric constant films	WONG, LAWRENCE D.
10802331	Not Issued	41	03/16/2004	Electron-beam treated CDO films	WONG, LAWRENCE D.
10802991	Not Issued	30	03/16/2004	Electron-beam treated CDO films	WONG, LAWRENCE D.
11037860	7192856	150	01/18/2005	FORMING DUAL METAL COMPLEMENTARY METAL OXIDE SEMICONDUCTOR INTEGRATED CIRCUITS	WONG, LAWRENCE D.
08978106	6057226	150	11/25/1997	AIR GAP BASED LOW DIELECTRIC CONSTANT INTERCONNECT STRUCTURE AND METHOD OF MAKING SAME	WONG, LAWRENCE D.
09001509	6083839	150	12/31/1997	UNIQUE CHEMICAL MECHANICAL PLANARIZATION APPROACH WHICH UTILIZES MAGNETIC SLURRY FOR POLISH AND MAGNETIC FIELDS FOR PROCESS CONTROL	WONG, LAWRENCE D.
09001547	5946601	150	12/31/1997	A UNIQUE a-C:N:H/a-C:NX FILM LINER/BARRIER TO PREVENT FLUORINE OUTDIFFUSION FROM a-FC CHEMICAL VAPOR DEPOSITION DIELECTRIC LAYERS	WONG, LAWRENCE D.

<del>09050707</del>	Not Issued	161	03/30/1998	A METHOD FOR FORMING AN INTERCONNECT SYSTEM USING A LOW DIELECTRIC CONSTANT LAYER	WONG, LAWRENCE D.
<del>09201580</del>	Not Issued	161	11/30/1998	STABILIZATION OF LOW DIELECTRIC CONSTANT FILM WITH IN SITU CAPPING LAYER	WONG, LAWRENCE D.
09352634	6284091	150	07/13/1999	UNIQUE CHEMICAL MECHANICAL PLANARIZATION APPROACH WHICH UTILIZES MAGNETIC SLURRY FOR POLISH AND MAGNETIC FIELDS FOR PROCESS CONTROL	WONG, LAWRENCE D.
09458547	6417098	150	12/09/1999	ENHANCED SURFACE MODIFICATION OF LOW K CARBON-DOPED OXIDE	WONG, LAWRENCE D.
10097328 no EB	Not Issued no OPI	41	03/15/2002	Method of making a semiconductor device using a damascene interconnect with a laminated dielectric	WONG, LAWRENCE D.
10105431	7214594	150	03/26/2002	METHOD OF MAKING SEMICONDUCTOR DEVICE USING A NOVEL INTERCONNECT CLADDING LAYER	WONG, LAWRENCE D.
10194523	7022478	150	07/11/2002	METHODS FOR EVALUATING STROKE OR CARDIAC ISCHEMIA BY NUCLEIC ACID DETECTION	WONG, LAWRENCE KA SING
60380719	Not Issued	159	05/14/2002	Methods for evaluating stroke or cardiac ischemia by nucleic acid detection	WONG, LAWRENCE KA SING

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